

## PATENT ABSTRACTS OF JAPAN

(11)Publication number : 2001-194790

(43)Date of publication of application : 19.07.2001

(51)Int.Cl.

G03F 7/039

H01L 21/027

(21)Application number : 2000-004306

(71)Applicant : TORAY IND INC

(22)Date of filing : 13.01.2000

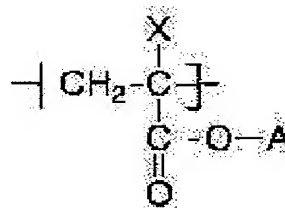
(72)Inventor : TAMURA KAZUTAKA  
NIO HIROYUKI  
OBAYASHI GENTARO

## (54) POSITIVE TYPE RADIATION SENSITIVE COMPOSITION

(57)Abstract:

PROBLEM TO BE SOLVED: To obtain a high sensitivity positive type radiation sensitive composition having such resolution as to attain sub-quarter-micron patterning.

SOLUTION: The positive type radiation sensitive composition contains a polymer containing a structural unit of formula 1 (where X is fluorine-containing alkyl; and A is a monovalent organic group having tertiary carbon combined to oxygen and containing an aromatic ring) and an acid generating agent which generates an acid when irradiated.



## LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]